

Improvements of wet chemical etch equipment (SAT) to support Infineon Zero Defect Strategy

Dr. Ursula Meyer; Infineon Austria AG

AGENDA:

- **Equipment Improvement - Motivation**
- **Levers & Modifications**
- **Targets & Results**



Our Team

- **Gerhard Wahl**; equipment engineer & system expert
- **Willi Schwarz**; process engineering
- **Ursula Meyer**; process engineering & project management
- **Michi Holzinger**; APC expert
- **Gernot Auer**; IT and system integration
- **Dieter Frank & Team**; IT

SAT equipment improvement - motivation

High throughput tool



SAT: Spray Acid Tool

Critical process application

Processes:

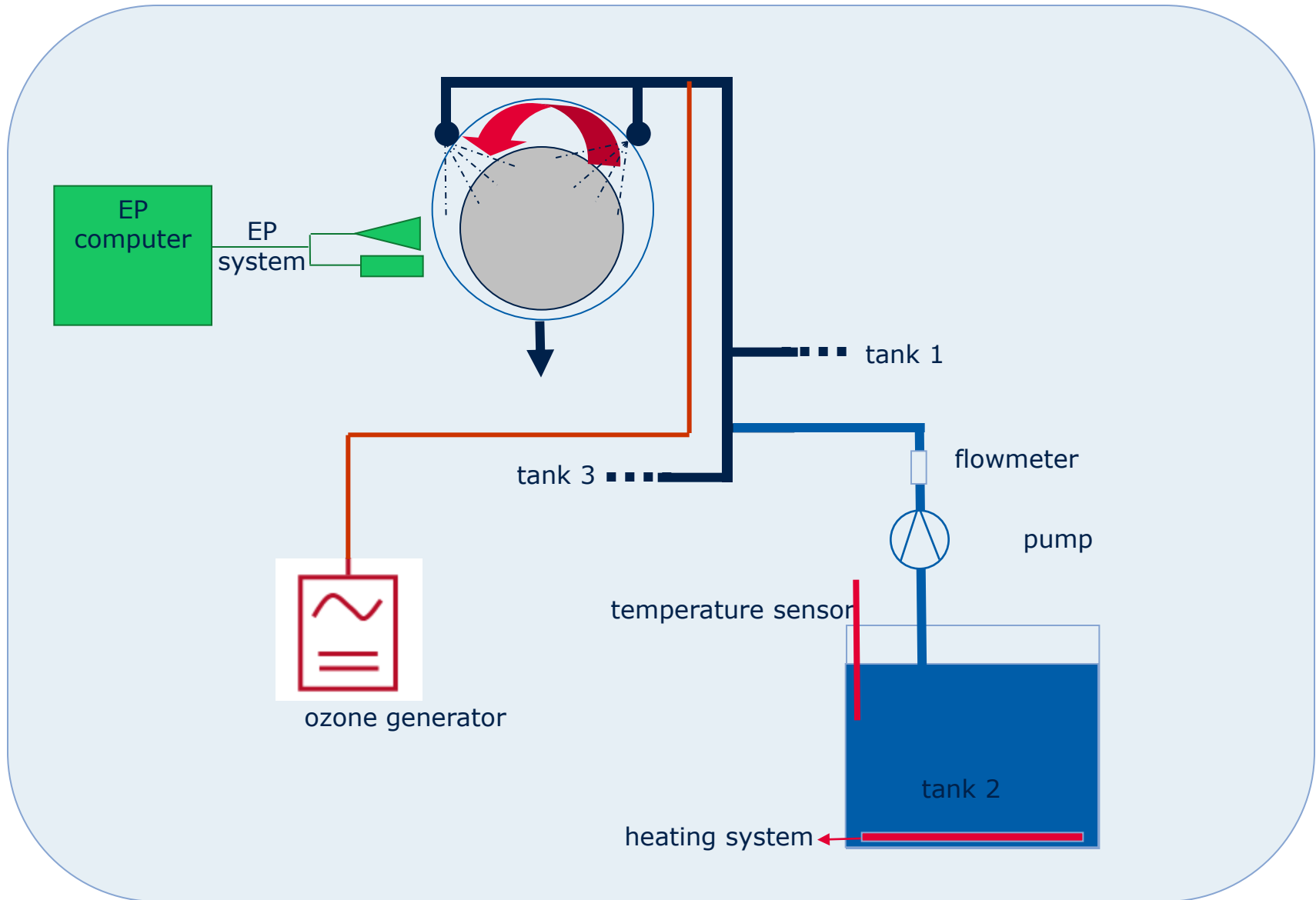
- Etching: Al, Si, Cu, W, TiW
- Resist removal
- Rinsing & Drying

Poor performance

Challenges:

- **Process stability:** cpk 30% below target
- **Equipment stability:** Unscheduled down > 10%
- **Wafer scrap:** 300% above target

SAT equipment improvement - motivation



Levers, Modifications & Targets

Levers & Modifications

- Bearingless **pumps** adapted and installed

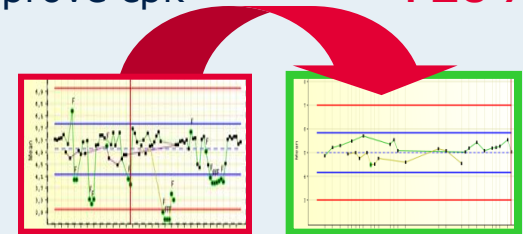


- New **sensors** integrated for temperature, chemistry, flow
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TARGETS & RESULTS

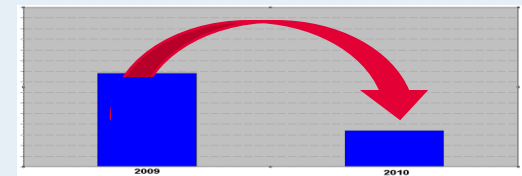
- **Process stability**

Improve cpk **+20%**



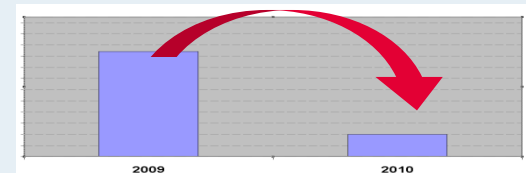
- **Equipment stability**

Reduce Equipment Down **-50%**

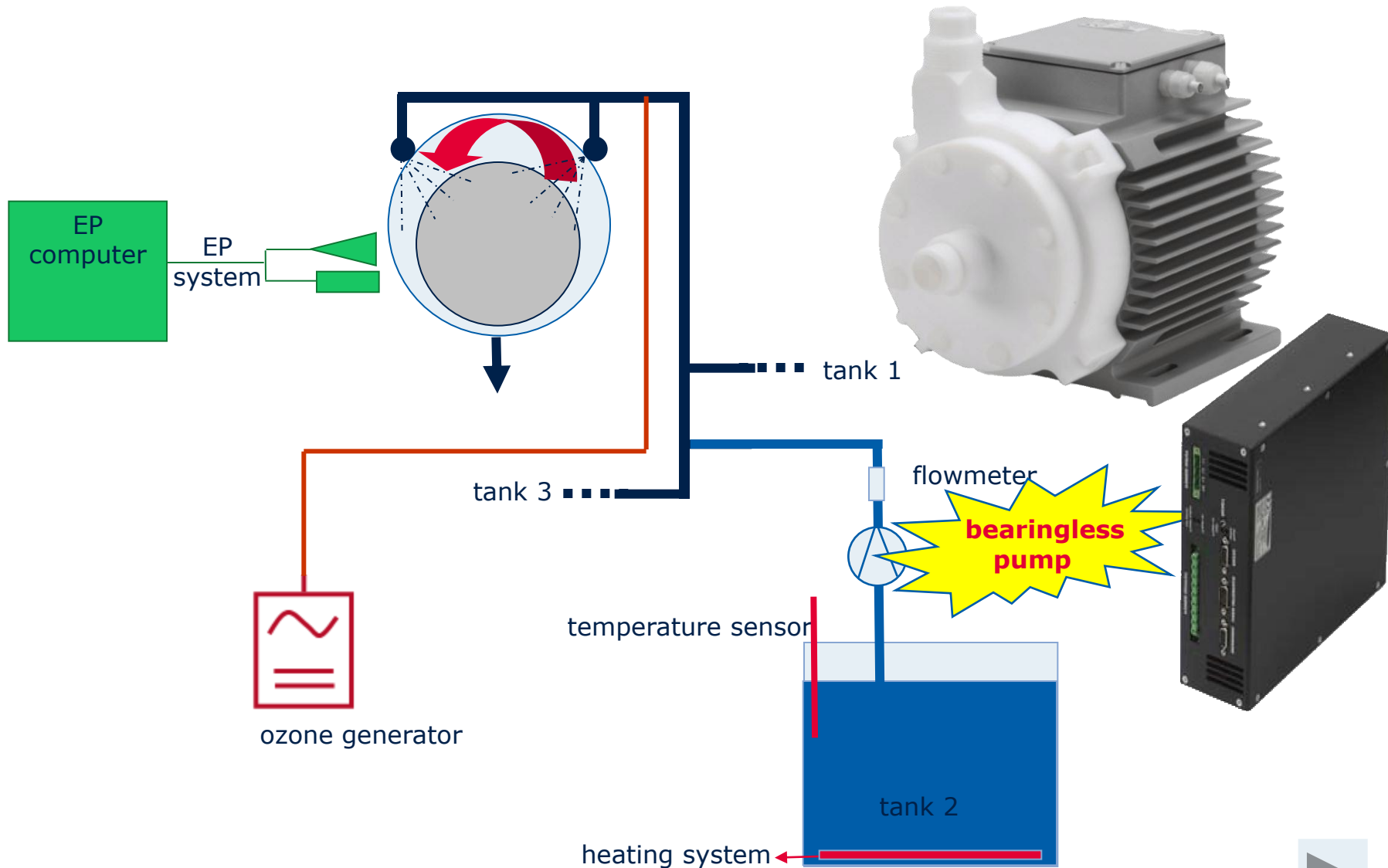


- **Wafer scrap**

Reduce Scrap ratio **-50%**



Complex and In-Depth Hardware Modification at SAT1D



Levers, Modifications & Targets

Levers & Modifications

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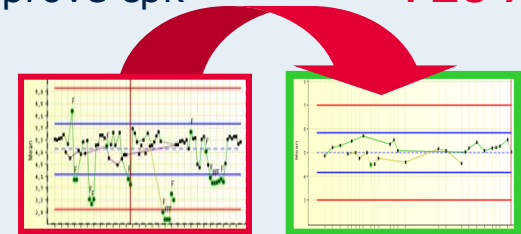
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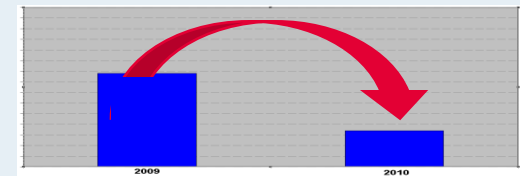
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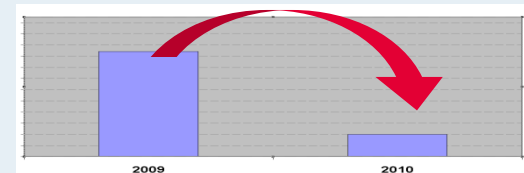
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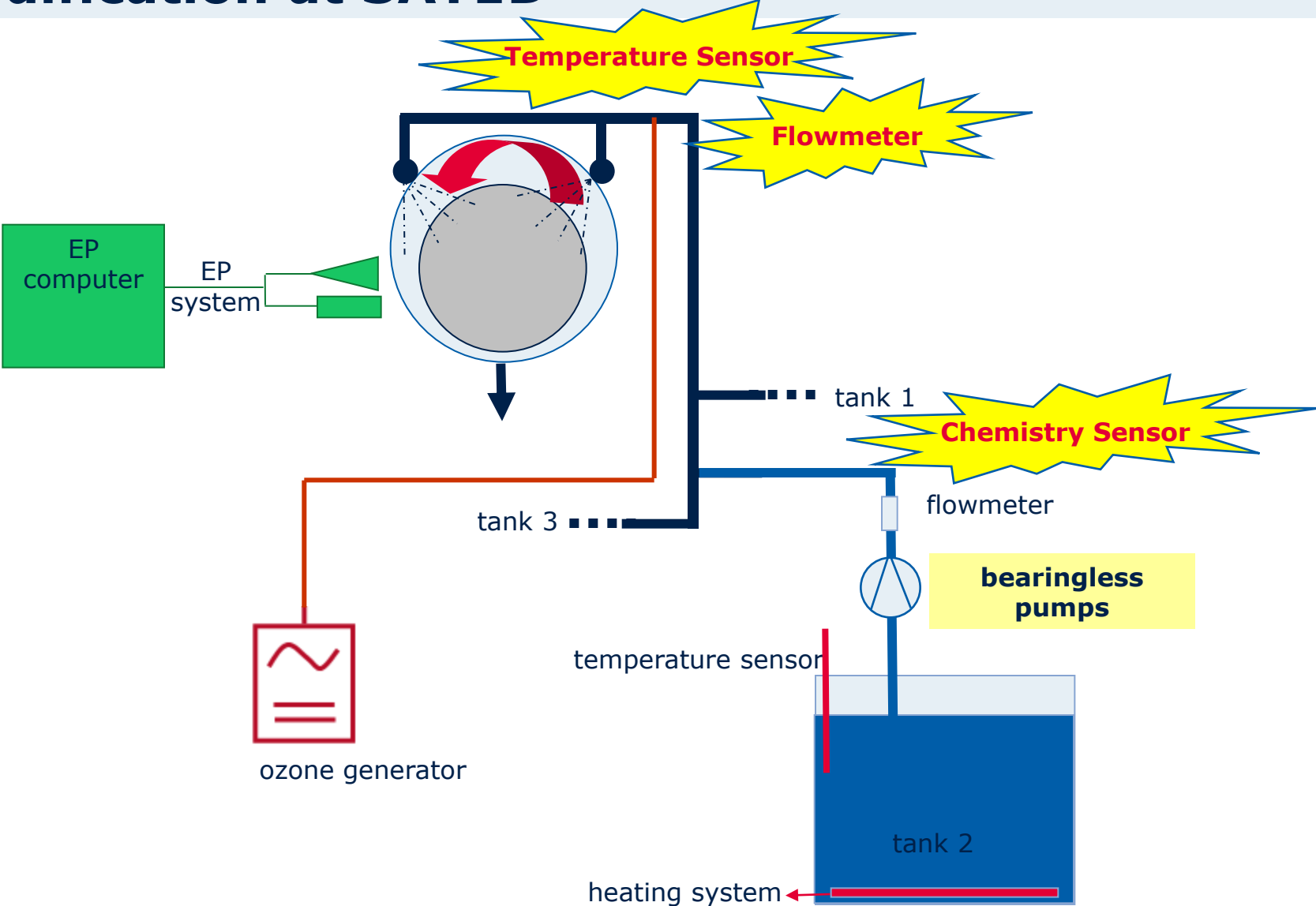
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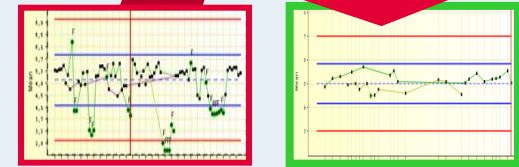
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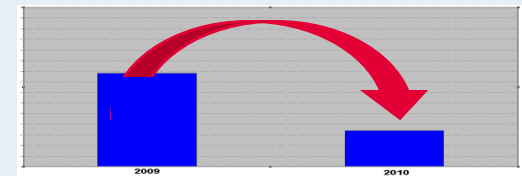
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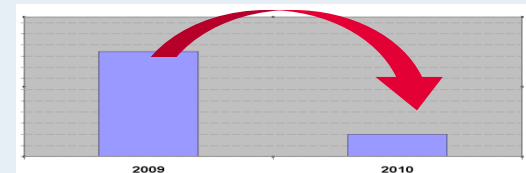
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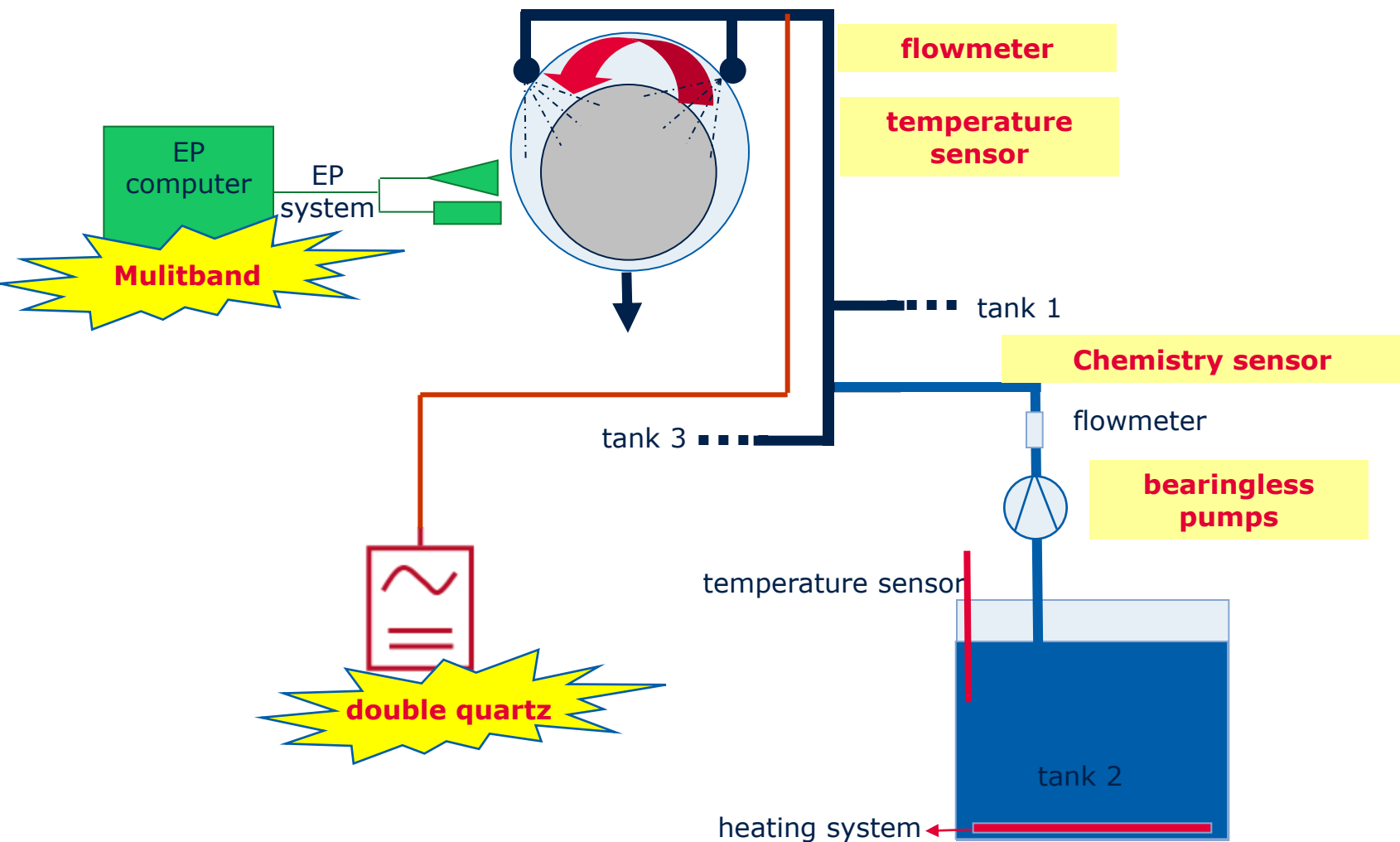
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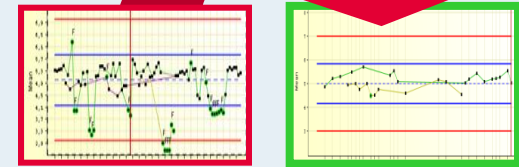
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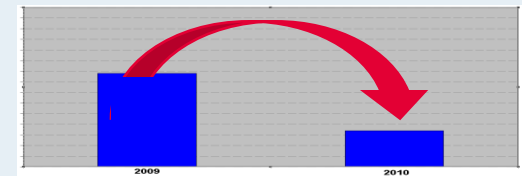
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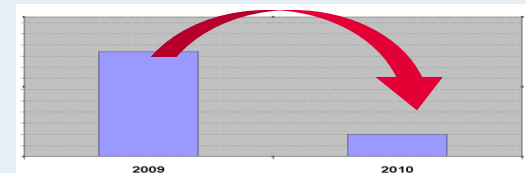
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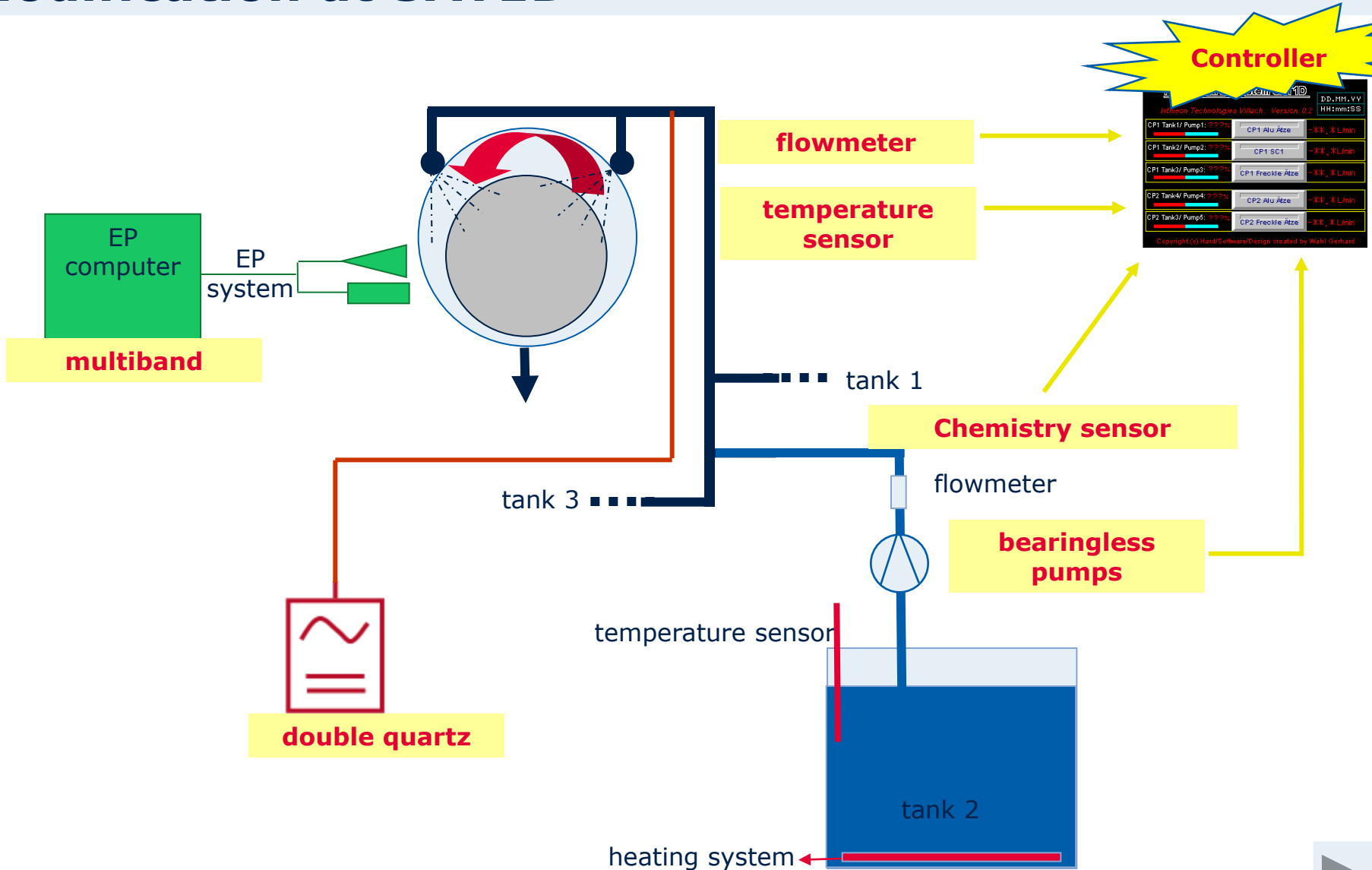
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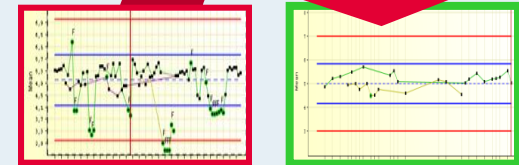
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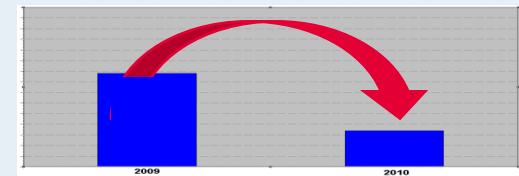
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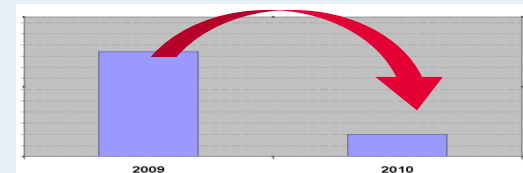
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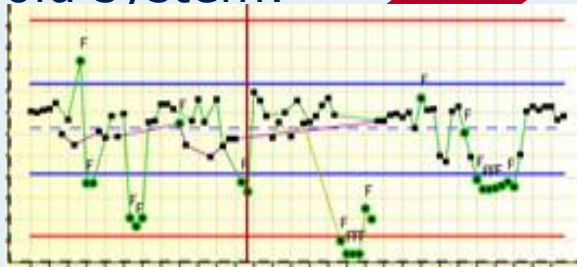
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Results process uniformity - cpk

Target +20%

old system:



CD Measurement

Result: +70%



samples by date

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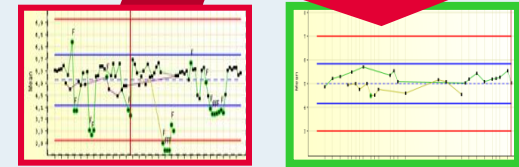
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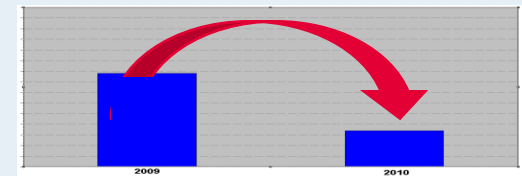
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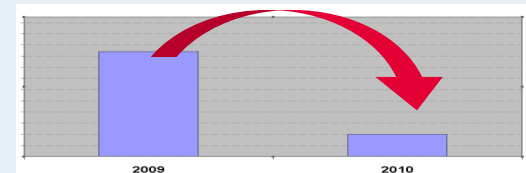
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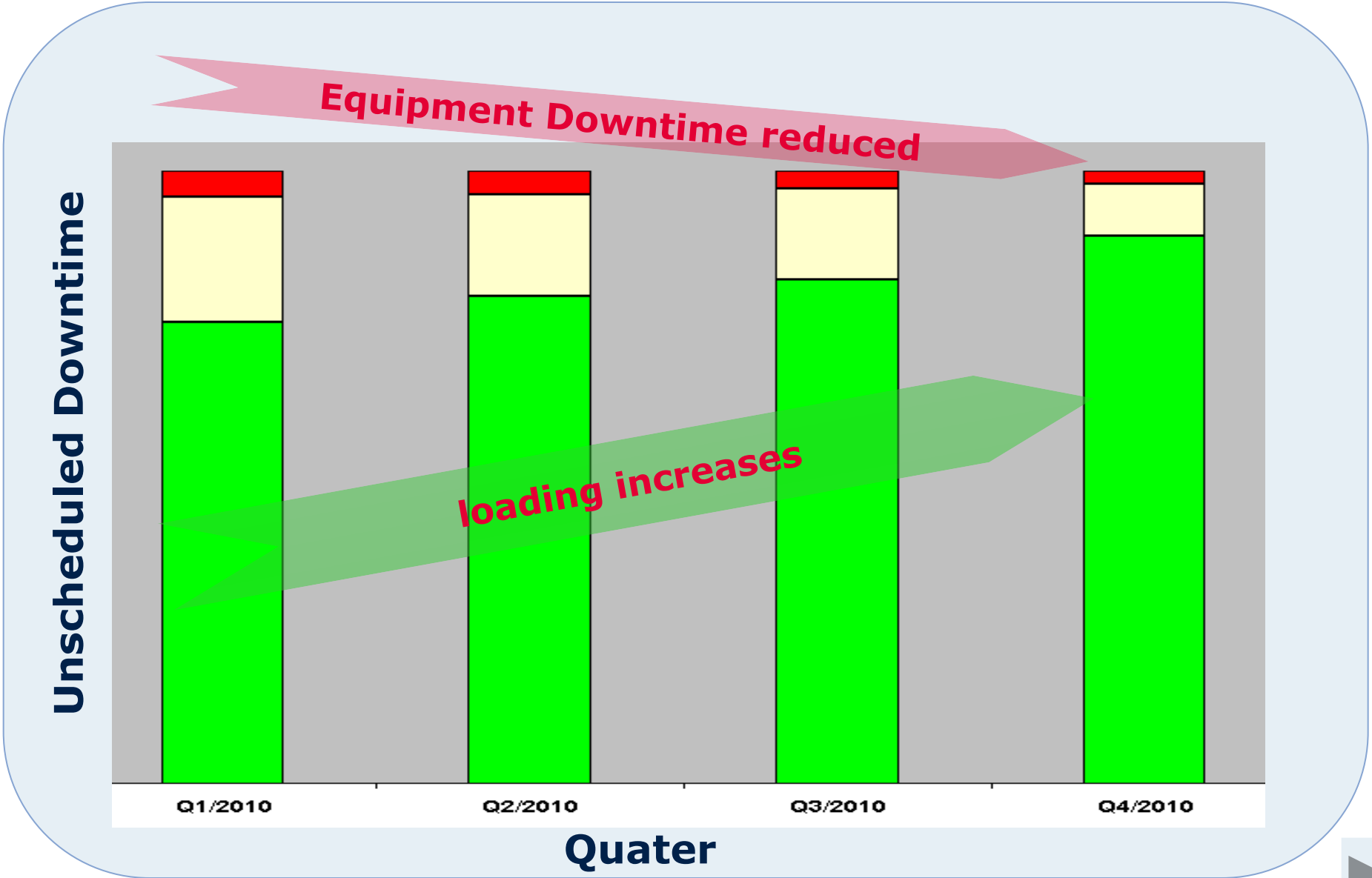
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Results Equipment Performance



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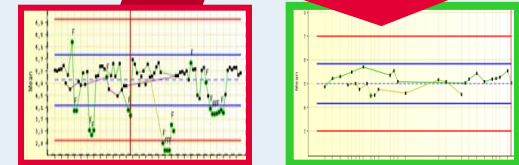
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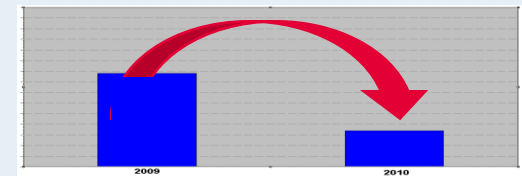
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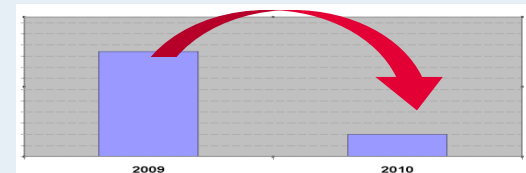
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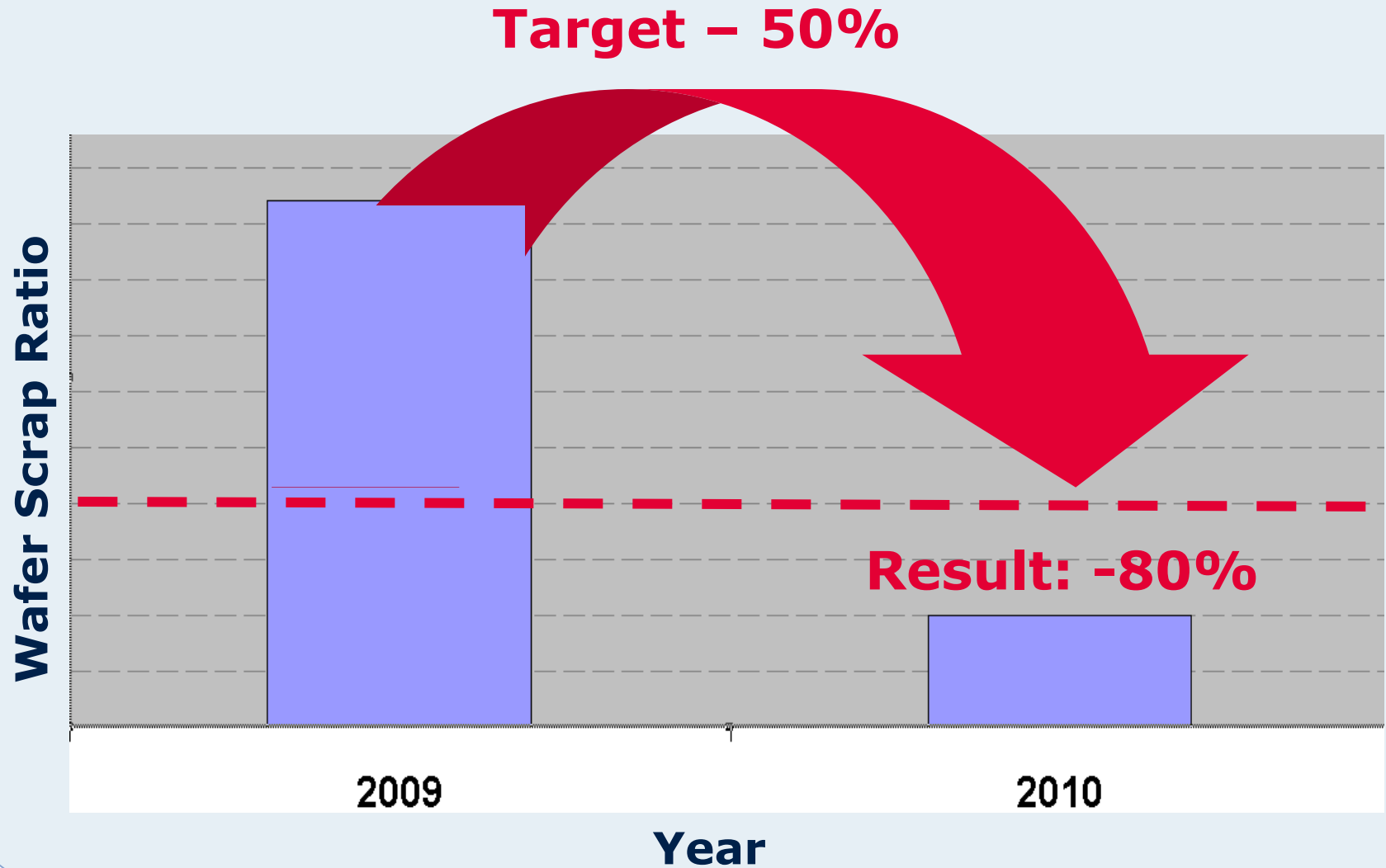
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Results Wafer Scrap





Thank you for your attention !



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